

In the Specification

Please amend the disclosure at pages 13-14, from line 16 on page 13 to line 10 on page 14, as follows:

As shown in FIG. 4, in a step ~~414a~~ 414b, in one embodiment, the carbon dioxide is optionally recycled. If the recycle option in step ~~414a~~ 414b is carried out, the carbon dioxide will be treated by application of suitable heat and pressure to render the carbon dioxide supercritical again, as shown in step 416. In one embodiment, the carbon dioxide is re-purified in, between or as a part of step ~~414a~~ 414b and/or as part of step 416. Following the step 416, the supercritical carbon dioxide may be provided to the step 408, as shown in FIG. 4.

In another embodiment, also shown as an option in step ~~414a~~ 414b, the carbon dioxide is simply released to the atmosphere. If the carbon dioxide is obtained from an industrial process which generates carbon dioxide and would otherwise release the carbon dioxide to the atmosphere, there is no net increase in atmospheric carbon dioxide as a result of such release from the present process.

It may be more desirable for a number of reasons, of course, to continue to recycle the carbon dioxide. For example, in one embodiment, the pressure of the carbon dioxide may be reduced below the critical pressure, but the pressure can be maintained at an elevated pressure relative to atmospheric pressure. By maintaining the pressure at an elevated level, less work will be required to increase the pressure to at least the critical pressure when the carbon dioxide is recycled for re-use as supercritical carbon dioxide. Thus, as will be understood, it will likely be more efficient to recycle the carbon dioxide as shown in step ~~414a~~ 414b and step 416, for use in the present process, than to start with new carbon dioxide which is presumably at a lower temperature and/or pressure.

As shown in FIG. 4, in a step ~~414b~~ 414a, in one embodiment, the immersion lithography medium recovered from the mixture can be recycled to the step 404, and applied to another semiconductor wafer.